

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (canceled)

Claim 2 (currently amended): A substrate treatment process ~~for removing organic matter existing on a substrate~~, comprising:

treating ~~[[said]]~~ a substrate having resist pieces adhered thereto with ozone-hydrogen water prepared by dissolving an ozone-containing gas and a hydrogen-containing gas in ultrapure water, or ozone hydrogen water prepared by mixing ozone water prepared by dissolving an ozone-containing gas in ultrapure water and hydrogen water prepared by dissolving a hydrogen-containing gas in ultrapure water, or treating said substrate with said ozone water and said hydrogen water at the same time.

Claims 3-20 (canceled)

Claim 21 (currently amended): A substrate treatment apparatus for a substrate, comprising:

a treatment vessel;

a substrate holder configured to rotate said substrate in a horizontal plane in said treatment vessel;

a nozzle unit ~~arranged~~ positioned in an upper ~~[[part]]~~ portion of said treatment vessel ~~such that~~ and configured to eject at least one ~~[[a]] liquid is downwardly fed over at least a~~ portion of said substrate covering a length substantially equal to or greater than a diameter of said substrate and a width smaller than the diameter of said substrate as said substrate is held on said substrate holder, said nozzle unit comprising a plurality of cells configured to be fed with the at least one liquid; and

a plurality of feed ~~[[line]]~~ lines configured to feed the at least one liquid to said ~~nozzle unit~~ plurality of cells, respectively; and

~~a chamber configured to enclose therein said apparatus in its entirety;~~

~~wherein said nozzle unit is constructed in a form of a bar such that as viewed in plan, the liquid ejected from said nozzle unit reaches, with an area range having a length not smaller than a diameter of said substrate and a width smaller than said diameter of said substrate.~~

Claim 22 (currently amended): A substrate treatment apparatus according to claim 21, ~~wherein further comprising an~~ said nozzle unit further comprises an ultrasonic wave generator ~~arranged in said nozzle unit~~ configured to apply ultrasonic waves to the at least one liquid.

Claim 23 (currently amended): A substrate treatment apparatus according to claim 22, wherein said ~~nozzle unit is provided with~~ plurality of cells comprises at least one flow channel for ozone water, at least one flow channel for hydrogen water ~~[[or]]~~ and at least one flow channel for ozone-hydrogen water, and said at least one flow channel for ozone water is shielded from the ultrasonic waves.

Claim 24 (new): A substrate treatment apparatus according to claim 21, wherein said plurality of cells are configured to be fed with ozone water, hydrogen water and ozone-hydrogen water, individually.

Claim 25 (new): A substrate treatment apparatus according to claim 24, wherein said nozzle unit further comprises a buffer plate partitioning one of the plurality of cells containing said ozone water and another one of the plurality of cells containing said hydrogen water or said ozone-hydrogen water.

Claim 26 (new): A substrate treatment apparatus according to claim 21, wherein said nozzle unit has a bar shape substantially corresponding to the portion of said substrate.

Claim 27 (new): A substrate treatment apparatus according to claim 21, further comprising a chamber entirely enclosing said treatment vessel, substrate holder, and nozzle unit.

Claim 28 (new): A substrate treatment apparatus according to claim 21, wherein said plurality of cells are formed by lateral partitions and longitudinal partitions.

Claim 29 (new): A substrate treatment apparatus according to claim 21, wherein said plurality of cells comprises a plurality of outlets for ejecting the at least one liquid, respectively.

Claim 30 (new): A substrate treatment apparatus according to claim 29, wherein said plurality of outlets are a plurality of spray nozzles.

Claim 31 (new): A substrate treatment apparatus according to claim 22, wherein said ultrasonic wave generator comprises at least one quartz rod.

Claim 32 (new): A substrate treatment process comprising treating a substrate having resist pieces adhered thereto with ozone water and hydrogen water at the same time or with ozone-hydrogen water.

Claim 33 (new): A substrate treatment process according to claim 32, wherein said treating comprises treating said substrate with said ozone-hydrogen water and said ozone-hydrogen water is prepared by dissolving an ozone-containing gas and a hydrogen-containing gas in ultrapure water or by mixing ozone water prepared by dissolving an ozone-containing gas in ultrapure water and hydrogen water prepared by dissolving a hydrogen-containing gas in ultrapure water.

Claim 34 (new): A substrate treatment process according to claim 32, wherein said treating comprises treating said substrate with said ozone water and said hydrogen water simultaneously, said ozone water is prepared by dissolving an ozone-containing gas in ultrapure water, and said hydrogen water is prepared by dissolving a hydrogen-containing gas in ultrapure water.